

ABSTRACT

In a method for reusing a waste liquid generated during an etching process wherein a copper article is etched while using an ammoniac alkaline cupric chloride etchant, by continuously and selectively extracting copper from the waste liquid by using an extraction solvent, the lowering of the etching rate due to a large amount of extraction solvent mixed into the regenerated etching liquid can be prevented. The waste etching liquid is regenerated by agitating and mixing the waste liquid and the extraction solvent together and then separating the mixture into the original components. The regenerated etching liquid having a reduced copper concentration is reused for the etching operation, while the extraction solvent containing copper is subjected to the back extraction so that copper therein is transferred to an aqueous solution of sulfuric acid and copper sulfate. Thereafter, the extraction solvent is rinsed while using a rinsing liquid such as cold water, hot water or dilute hydrochloric acid to remove sulfuric acid from the extraction solvent.